L Number	Hits		DB	Time stamp
1	16	surface near9 (treat\$9 modif\$9 functional\$9) near9 filler and	USPAT;	2003/01/09 13:1
		(plasma glow discharge) near9 (polymeri\$ation polymeri\$ing	US-PGPUB;	
		polymeri\$1ed graft\$5)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
3	3	(amino near3 functional\$9) near9 filler same (epoxy epoxide) near9	USPAT;	2003/01/09 13:2:
	_	(resin mo\$11d\$5) same (react\$5 covalent\$5 chemical\$6)	US-PGPUB;	2003/01/07 13.2.
		(10001 1100 1100) Saine (100010 COVIDENCE)	EPO; JPO;	
			DERWENT;	
2	5	(amino near3 functional\$9) near9 filler same (epoxy epoxide) same	IBM_TDB	2002/01/00 12 2
2		(react\$5 covalent\$5 chemical\$6)	USPAT;	2003/01/09 13:3
		(Teactas covatentas chefficatas)	US-PGPUB;	
			EPO; JPO;	ļ
			DERWENT;	
			IBM_TDB	
4	0	"4786415" and (epoxy epoxide)	USPAT;	2003/01/09 13:34
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM TDB	
5	25	"4786415"	USPAT;	2003/01/09 16:10
			US-PGPUB;	2003/01/07 10.10
			EPO, JPO,	
	ł			
			DERWENT;	
6	0	"4786415" and filler	IBM_TDB	
0	U	4780415 and mier	USPAT;	2003/01/09 13:35
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
_	_		IBM_TDB	
7	0	plasma and introduc\$4 near9 monomer near9 steel near9 pipe	USPAT;	2003/01/09 16:11
			US-PGPUB;	
ĺ			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
9	1	plasma near9 reactor same steel near9 pipe	USPAT;	2003/01/09 16:13
			US-PGPUB;	2003/01/07 10:13
			EPO; JPO;	ļ
			DERWENT;	
10	1	plasma same steel near9 pipe with monomer	IBM_TDB	2002/01/00 16 15
10	1	plasma same sieer nears pipe with monomer	USPAT;	2003/01/09 16:15
	į	1	US-PGPUB;	
1			EPO; JPO;	
			DERWENT;	
11	_ [		IBM_TDB	
11	1	plasma and steel near9 pipe with monomer	USPAT;	2003/01/09 16:15
	]		US-PGPUB;	
	ŀ		ЕРО; ЈРО;	
ĺ			DERWENT;	
			IBM_TDB	
8	291	plasma same steel near9 pipe	USPAT;	2003/01/09 16:15
		·	US-PGPUB;	_000,01,07 10,13
			EPO; JPO;	
			DERWENT;	
12	,,,	-1	IBM_TDB	
12	181	plasma with steel near9 pipe	USPAT;	2003/01/09 16:16
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT,	
ł			IBM_TDB	

13	100			T = = = = = = = = = = = = = = = = = = =
13	129	plasma near9 steel near9 pipe	USPAT;	2003/01/09 16:17
			US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
14	16	(plasma same steel near9 pipe) same inject\$6	USPAT;	2003/01/09 16:18
1 1	10	(plasma same steer hear) pipe) same injectato	US-PGPUB;	2003/01/09 10.18
			EPO; JPO;	
			DERWENT:	
			IBM_TDB	Ì
15	10	(plasma with steel near9 pipe) with inject\$6	USPAT;	2003/01/09 16:27
			US-PGPUB,	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	!
16	0	"5843789" and steel	USPAT;	2003/01/09 16:28
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
17		"5843789"	IBM_TDB	0000001000000
17	8	J043/67	USPAT;	2003/01/09 16:29
			US-PGPUB;	
	į		EPO; JPO; DERWENT;	
			IBM_TDB	
18	0	"6428861" and steel	USPAT;	2003/01/09 16:30
		0 120001 und Steel	US-PGPUB;	2003/01/09 10.30
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
19	2	"6428861"	USPAT;	2003/01/09 17:22
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT,	
			IBM_TDB	
20	3746	(microwave (radio near2 frequency)) near9 power near9 plasma	USPAT;	2003/01/09 17:24
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
21	275	((microsycus (modic mon2 for mon2))	IBM_TDB	
41	213	((microwave (radio near2 frequency)) near9 power near9 plasma) near9 watt	USPAT;	2003/01/09 17:37
		near / watt	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
22	34	(((microwave (radio near2 frequency)) near9 power near9 plasma)	USPAT;	2003/01/09 17:25
	-	near9 watt) near9 ("10" "40")	US-PGPUB;	2003/01/07 17.23
		,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
23	30	((microwave (radio near2 frequency)) near9 power near9 plasma)	USPAT;	2003/01/09 20:00
		near9 ("10" "40") near3 watt	US-PGPUB;	
-	,	-	EPO, JPO,	
			DERWENT;	
			IBM_TDB	
24	384	(plasma glow discharge) near9 (polymeri\$ation polymeri\$ing	USPAT;	2003/01/09 17:36
		polymeri\$1ed graft\$5) near9 power	US-PGPUB;	
			ЕРО; ЈРО;	
1			DERWENT;	
			IBM_TDB	

25	354	Language Production Programme Contraction Pr	USPAT;	2003/01/09 17:36
		near9 power	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
26	42		IBM_TDB	2002/01/00 17 17
26	43	1 / Language (Landanian Landanian P. Landanian P. Landanian Landan	USPAT;	2003/01/09 17:37
		graft\$5) near9 power ) near9 watt	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
27	2	4374717.pn.	USPAT;	2003/01/09 20:00
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	350	(yoon roh).in. and plasma	USPAT;	2003/01/08 19:10
	1		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	1	((yoon near3 tae-ho) (roh near3 joon)).in. and plasma	USPAT;	2003/01/08 19:04
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	9	(kwangju).as. and plasma	USPAT;	2003/01/08 19:08
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	34	((yoon roh).in. and plasma) and silica	USPAT;	2003/01/08 19:08
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	1512	(kwangju).as.	USPAT;	2003/01/08 19:08
	1		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
		l	IBM_TDB	
-	34	(((yoon roh).in. and plasma) ((kwangju).as. )) and plasma and silica	USPAT;	2003/01/08 19:10
			US-PGPUB;	
			EPO; JPO;	
**			DERWENT;	
			IBM_TDB	
-	16091	(yoon roh).in.	USPAT;	2003/01/08 19:10
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
	<u></u>		IBM_TDB	
-	17557	((kwangju).as.)((yoon roh).in.)	USPAT;	2003/01/08 19:10
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
		<u></u>	IBM_TDB	
-	121	(((kwangju).as.) ((yoon roh).in.)) and plasma same (silica (silicon	USPAT;	2003/01/08 19:13
		(dioxide oxide)))	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	

Cidoxide coxide )) same modif\$6					
FPO_IPO_DERWENT_	-	1	(((kwangju).as.) ((yoon roh).in.)) and plasma same (silica (silicon	USPAT;	2003/01/08 19:12
102   (plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   USPAT, USP			(dioxide oxide))) same modif\$6		
102   (plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8)   (plasma near9 (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8)   (plasma near9 (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8)   (plasma near9 (silica (silicon near2 (dioxide oxide))   (plasma near9 polymeri\$8)   (plas					
102   (plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   USPAT, USPGPUB, EPO, IPO, DERWENT, IBM TDB USPAT, US		·			
same modif\$8  ((plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide))) same (surface near3 modif\$8)  ((plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide))) same (surface near3 modif\$8))  ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) same (surface near3 modif\$8))  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))))  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (particle particulate)  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8		102	( (nlagma mand malamanido) anna (-ilian (-ilian (1)   1   1   1   1   1   1   1   1   1		2002/01/02 10 20
Compared to the content of the con	-	102			2003/01/08 19:20
- 1 ((plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))   DERWENT, IBM, TIDB US-PGPUB, EPO, IPO, DERWENT, IBM, TIDB US-P			Same modita		
1   1   1   1   1   1   1   1   1   1					
Comparison   Com	İ	1		1	
Same (surface near3 modif\$8)	1_	56	((nlasma near0 nolumeri\$9) some (cilian (cilian (diavide evide))))	_	2002/01/00 10-22
1			1		2003/01/08 19:23
1		f	Same (same near s modify)		
1					
1					
Same (surface near3 modif\$8)) same (particle particulate)	-	1	(((plasma near9 polymeri\$8) same (silica (silicon (dioxide oxide)))		2003/01/08 10:20
Pro, JPO, DERWENT, BM, TDB (ylasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (silica (silicon near2 (dioxide oxide)))   Same (particle particulate)   Same (particulate)   Same (parti					2003/01/08 17:20
DERWENT;   IBM_TDB   USP-AT;   USP-GPUB;   EPO, IPO, DERWENT;   USP-GPUB;   EPO, IPO, DERWENT;   IBM_TDB   USP-AT;   USP-GPUB;   EPO, IPO, DERWENT;   IBM_TDB   USP-AT;   USP-GPUB;   EPO, IP			, man (and an and an and an and an		
BIM_TDB					
18					
Oxide ))	-	358	(plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide		2003/01/08 19:27
- 20 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (particle particulate)  - 18 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same modif\$8 ((plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide)))) same modif\$8 ((plasma near9 polymeri\$8)) and (silica (silicon near2 (dioxide oxide)))) near9 (surface near3 modif\$8)  - 13 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide)))) near9 (surface near3 modif\$8)  - 15 ((plasma near9 polymeri\$8)) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - 16 2 4 (27/488.ccls. and (silica (silicon near2 (dioxide oxide)))) near9 (surface near3 modif\$9)  - 16078 plasma and (silica (silicon near5 (dioxide oxide)))) near9 (surface near6) (surface near7) modif\$9  - 16078 plasma and (silica (silicon near5 (dioxide oxide)))) near9 (surface near6) (dioxide oxide)))) near9 (surface near7) (surface near7) modif\$9  - 16078 plasma and (silica (silicon near5 (dioxide oxide)))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol) (surface) (surface near6) (surface near7) (surface near7) (surface near9) (dioxide near9) (surface near9			oxide)))		
- 20 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) ) same (particle particulate)  - 18 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same modif\$8 ((plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide)))) part polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - 13 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide)))) part polymeri\$8) same (silica (silicon near2 (dioxide oxide))) part polymeri\$8) part polymeri\$8) same (silica (silicon near2 (dioxide oxide))) part polymeri\$8) part polymeri\$8) same (silica (silicon near2 (dioxide oxide))) part polymeri\$8) part polymeri\$8) same (silica (silicon near2 (dioxide oxide))) part polymeri\$8) part polymeri\$8) part polymeri\$8) part polymeri\$8) same (silica (silicon near2 (dioxide oxide))) part polymeri\$8) part pol		1		•	
20					
Coxide   C					
- 18 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same modif\$8 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8) (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8) (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (sil	-	20	((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide		2003/01/08 19:20
- 18 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same modif\$8  - 13 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - 2 5 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - 3 5 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - 4 4 (27/488.ccls. and (silica (silicon near2 (dioxide oxide)))) near9  - 4 4 427/488.ccls. and (silica (silicon near2 (dioxide oxide)))) near9  - 4 4 427/488.ccls. and (silica (silicon near2 (dioxide oxide)))) near9  - 4 4 427/488.ccls. and (silica (silicon near3 (dioxide oxide)))) near9  - 5 modif\$9  - 16078			oxide)))) same (particle particulate)	US-PGPUB;	
18				EPO, JPO;	
18    ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))   same modif\$8				DERWENT;	
oxide)))) same modif\$8  (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) same (surface near3 modif\$8)  (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) uspar; lbM_TDB uspar; l				IBM_TDB	
- 13 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - 5 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (pro, pro, pdr. pro, polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (pro, pro, pdr. pro, polymeri\$9)  - 4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 (pro, pro, pdr. pro, polymeri\$9)  - 4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 (pro, pro, pdr. pro, polymeri\$9)  - 4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 (pro, pro, pdr. pro, pdr. pro, pdr. pro, pdr. pro, pdr. pro, pdr. pro, pdr. pro, p	] -	18		USPAT;	2003/01/08 19:20
- 13 (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - 5 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - 4 (27/488 ccls. and (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 4 (427/488 ccls. and (silica (silicon near5 (dioxide oxide))) near9 (modif\$9)  - 4 (427/488 ccls. and (silica (silicon near5 (dioxide oxide))) near9 (modif\$9)  - 5 ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 6 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 7 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 8 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silica (silicon near2 (dioxide oxide))) near9 (modif\$9)  - 10 (plasma near9 polymeri\$8) same (silica (silica (silica (silica (s	ĺ		oxide)))) same modif\$8	* 1	
- (plasma near9 polymeri\$8) and (silica (silicon near2 (dioxide oxide))) near9 (surface near3 modif\$8)  - (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica (silica (silicon near2 (dioxide oxide))) near9 (plasma near9 polymeri\$8) same (silica					
13					ļ
oxide))) near9 (surface near3 modif\$8)  US-PGPUB; EPO, JPO, DERWENT; IBM_TDB US-PGPUB; EPO, JPO, DERWENT; ISM_TDB US-PGPUB		12	(-1		
- ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) near9 (DERWENT; IBM_TDB_EPO; JPO; DERWENT; IBM_TDB_USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB_US-PGPUB; EPO; JPO; DERWENT; IBM_TDB_US-PGP	-	13			2003/01/08 19:24
- ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) same (surface near3 modif\$8)  - ((plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide)))) near9 (USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISPO; JPO; JPO; DERWENT; ISPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO; J			oxide))) hear9 (surface near3 modif\$8)		
- (plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) ) same (surface near3 modif\$8)  4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 227/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 227/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 227/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 227/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  5 0003/01/08 19:24  18M_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;					
(plasma near9 polymeri\$8) same (silica (silicon near2 (dioxide oxide))) ) same (surface near3 modif\$8)  4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISPO; J					
oxide)))) same (surface near3 modif\$8)  US-PGPUB; EPO, JPO, DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISPO; JPO; JPO; DERWENT; JPO; JPO; DERWENT; JPO; JPO; JPO; DERWENT; JPO; JPO; JPO; JP	_	5	((nlasma near9 nolymeritt) come (cilica (cilican near) (dianid-		2002/01/09 10:24
4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 2003/01/08 19:28 USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; DERWENT;					2003/01/08 19:24
- 4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 2003/01/08 19:28 USPAT; US-PGPUB; EPO, JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, JPO; DERWENT; US-PGPUB; EPO, JPO; DERWENT; US-PGPUB; EPO, JPO; DERWENT;			))) / same (same near) mountain)	<i>'</i>	ļ
4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9  4 227/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9  5 2003/01/08 19:28  16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)					
4 427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9			•		
modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  4 27/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 modif\$9  US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;	-	4	427/488.ccls. and (silica (silicon near2 (dioxide oxide))) near9		2003/01/08 19:28
- 4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9					
- 4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9					
4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9 USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; USPGPUB; EPO; JPO; DERWENT;					
4 427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9					
modif\$9  US-PGPUB; EPO, JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, JPO; DERWENT; USPAT; US-PGPUB; EPO, JPO; DERWENT; US-PGPUB; EPO, JPO; DERWENT; DERWENT; DERWENT; DERWENT; DERWENT;	-	4	427/488.ccls. and (silica (silicon near5 (dioxide oxide))) near9		2003/01/08 19:34
- 16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; DERWENT;		ĺ			
- 16078 plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;			et a constant of the constant		İ
- land plasma and (silica (silicon near5 (dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  USPAT; USPAT; USPAT; USPAT; USPAT; DERWENT;					
diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)  US-PGPUB; EPO; JPO; DERWENT;					
EPO; JPO; DERWENT;	-	16078	plasma and (silica (silicon near5 (dioxide oxide))) and (amine	USPAT;	2003/01/09 09:30
DERWENT;			diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol)	· 1	
IBM_TDB					
				IBM_TDB	

-	552		USPAT;	2003/01/08 19:37
		(dioxide oxide))) and (amine diamino\$9 allyl\$1amine pyrrole	US-PGPUB;	
		allyl\$1mercaptan allyl\$1alcohol)	EPO; JPO;	Í
	1		DERWENT;	
			IBM_TDB	İ
-	539		USPAT;	2003/01/08 19:38
	ĺ	allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol) same plasma	US-PGPUB;	
1			EPO; JPO;	
	İ		DERWENT;	
			IBM_TDB	
-	274		USPAT;	2003/01/09 09:55
İ		(amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan	US-PGPUB;	
		allyl\$1alcohol) same plasma	EPO, JPO,	
			DERWENT;	
			IBM TDB	
-	44	( are the contract ( are the contract)) but it ( but it to contract)	USPAT;	2003/01/08 19:44
		same (amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan	US-PGPUB;	2000.01,000 15.11
	ĺ	allyl\$1alcohol) same plasma	ЕРО; ЛРО;	
			DERWENT;	İ
	İ		IBM_TDB	
_	18	(silica (silicon near5 (dioxide oxide))) same (surface substrate) and	USPAT;	2003/01/08 19:45
ļ	İ	(amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan	US-PGPUB;	2003/01/08 19:43
		allyl\$1alcohol) with plasma with polymeri\$9		
		any to record y with plasma with polyments	ЕРО; ЛРО;	
			DERWENT;	
1_	0	(plasma disharaa alaw) sama (makumani80 885)	IBM_TDB	
-	"	(plasma dicharge glow) same (polymeri\$9 graft\$5) same (monomer	USPAT;	2003/01/09 09:32
		amine diamino\$9 allyl\$1amine pyrrole allyl\$1mercaptan	US-PGPUB;	
		allyl\$1alcohol) and (silica (silicon near5 (dioxide oxide)))	EPO; JPO;	
			DERWENT;	
	2764	Coiling Coilings were City 11 11 11 11 11	IBM_TDB	
-	3764	(silica (silicon near5 (dioxide oxide))) near9 (particle particulate)	USPAT;	2003/01/09 10:56
	1	same surface near9 (treat\$9 modif\$9)	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
İ	400	// ''' / '''	IBM_TDB	
] <del>-</del>	409	((silica (silicon near5 (dioxide oxide))) near9 (particle particulate)	USPAT;	2003/01/09 10:00
		same surface near9 (treat\$9 modif\$9) ) and (amine diamin\$9	US-PGPUB;	
		allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol) and (plasma	ЕРО; ЛРО;	
		glow discharge)	DERWENT;	
			IBM_TDB	
-	19	((silica (silicon near5 (dioxide oxide))) near9 (particle particulate)	USPAT;	2003/01/09 10:20
		same surface near9 (treat\$9 modif\$9) ) and (amine diamin\$9	US-PGPUB;	
		allyl\$1amine pyrrole allyl\$1mercaptan allyl\$1alcohol) and (plasma	ЕРО; ЛРО;	
		glow discharge) near9 (polymeri\$1ation polymer\$2ing graft\$5)	DERWENT;	
			IBM_TDB	
-	2	"2000143230"	USPAT;	2003/01/09 10:09
			US-PGPUB;	
	]		ЕРО; ЛРО;	
			DERWENT;	
			IBM TDB	
-	5270	(silica (silicon near5 (dioxide oxide))) near9 (particle particulate	USPAT;	2003/01/09 10:19
	ļ l	bead) near9 (treat\$9 modif\$9)	US-PGPUB;	2003/01/07 10.19
			EPO; JPO;	ţ
			DERWENT;	ļ
			IBM TDB	į
-	o	((silica (silicon near5 (dioxide oxide))) near9 (particle particulate		2002/01/00 10:21
		bead) near9 (treat\$9 modif\$9)) and (diamino\$1propane	USPAT;	2003/01/09 10:21
		diamino\$1alkane allyl\$1amine pyrrole allyl\$1mercaptan	US-PGPUB;	
		ally (\$1 alcohol) and (plasma along discharge) ====0 (==1=====0.	EPO; JPO;	
		allyl\$1alcohol) and (plasma glow discharge) near9 (polymeri\$1ation polymer\$2ing graft\$5)	DERWENT;	
	<u> </u>	horamerasing Ristras)	IBM_TDB	

···	<del></del>			
-	51	(diamino\$1propane diamino\$1alkane ally1\$1amine pyrrole	USPAT;	2003/01/09 10:22
	Ī	allyl\$1mercaptan allyl\$1alcohol) same (plasma glow discharge)	US-PGPUB;	
		near9 (polymeri\$1ation polymer\$2ing graft\$5)	EPO; JPO;	
	ļ		DERWENT;	
	İ		IBM_TDB	
-	3321	(epoxy glycidyl) near5 resin same (amin\$1 mercapto hydroxy\$1)	USPAT;	2003/01/09 10:49
		same (covalent\$6 chemical\$4)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	533	(epoxy glycidyl) near5 resin same (amin\$1 mercapto hydroxy\$1)	USPAT;	2003/01/09 10:50
		same (covalent\$6 chemical\$4) near5 (react\$8 bond\$6 attach\$4)	US-PGPUB;	2003/01/07 10.50
		( The second of the second of	EPO, JPO,	
			DERWENT;	
			IBM_TDB	
1-	146	(epoxy glycidyl) near9 resin near9 (amin\$1 mercapto hydroxy\$1)	USPAT;	2003/01/09 10:51
		near9 (covalent\$6 chemical\$4) near9 (react\$8 bond\$6 attach\$4)	US-PGPUB;	2003/01/09 10:31
		(leacted bollago attachie4)		
			EPO; JPO;	
			DERWENT;	
_	148	(epoxy glycidyl) near9 (mo\$11d\$3 resin) near9 (amin\$1 mercapto	IBM_TDB	2002/01/02 12 ==
	140	history (1) nearly (most loss festin) nearly (amin's mercapto	USPAT;	2003/01/09 10:53
		hydroxy\$1) near9 (covalent\$6 chemical\$4) near9 (react\$8 bond\$6	US-PGPUB;	
		attach\$4)	EPO; JPO;	
			DERWENT,	
	,	//1 '11'	IBM_TDB	
-	2	((epoxy glycidyl) near9 (mo\$1ld\$3 resin) near9 (amin\$1 mercapto	USPAT;	2003/01/09 10:55
		hydroxy\$1) near9 (covalent\$6 chemical\$4) near9 (react\$8 bond\$6	US-PGPUB;	
		attach\$4)) not ((epoxy glycidyl) near9 resin near9 (amin\$1 mercapto	ЕРО; ЈРО;	
	]	hydroxy\$1) near9 (covalent\$6 chemical\$4) near9 (react\$8 bond\$6	DERWENT;	
		attach\$4))	IBM_TDB	
-	3358	surface near9 (treat\$9 modif\$9) near9 (filler particle particulate)	USPAT;	2003/01/09 11:12
		and (silica (silicon near5 (dioxide oxide))) and mo\$1ld\$4	US-PGPUB;	
1			ЕРО, ЛРО,	
	i		DERWENT,	
Ī			IBM TDB	
-	58	surface near9 (treat\$9 modif\$9) near9 (silica (silicon near5 (dioxide	USPĀT;	2003/01/09 11:01
		oxide))) near9 filler same mo\$1ld\$4	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	19	(surface near9 (treat\$9 modif\$9) near9 (silica (silicon near5	USPAT;	2003/01/09 11:01
		(dioxide oxide))) near9 filler same mo\$11d\$4) same epoxy	US-PGPUB;	2005/01/05 11.01
		,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	EPO; JPO;	
		i	DERWENT;	
į į			IBM TDB	
_	695	surface near9 (treat\$9 modif\$9) near9 (filler particle particulate)		2002/01/00 12:23
]	0,5	and (silican near5 (dioxide oxide))) and mo\$11d\$4 and	USPAT;	2003/01/09 12:21
[	Ţ	(plasma glow discharge)	US-PGPUB;	İ
	Ī	(humana grow discissise)	ЕРО; ЛРО;	
			DERWENT;	
	32	overfood moon() (***********************************	IBM_TDB	
-	32	surface near9 (treat\$9 modif\$9) near9 (filler particle particulate)	USPAT;	2003/01/09 11:32
	ļ	near9 (plasma glow discharge) and (silica (silicon near5 (dioxide	US-PGPUB;	1
	ĺ	oxide))) and mo\$1ld\$4	EPO; JPO;	
			DERWENT;	ļ
	ļ	_	IBM_TDB	Ì
-	0	surface near9 (treat\$9 modif\$9) near9 filler same (plasma glow	USPĀT;	2003/01/09 11:41
l		discharge) near9 (polymeri\$ation polymeri\$ing polymeri\$1ed	US-PGPUB;	
[	1	graft\$5) and (silica (silicon near5 (dioxide oxide)))	ЕРО; ЛРО;	
]			DERWENT,	
			IBM_TDB	
				<del></del>

	· · · · · · · · · · · · · · · · · · ·			,
-	4	(por)mentation	USPAT;	2003/01/09 12:21
	1	polymeri\$ing polymeri\$1ed graft\$5) and (silica (silicon near5	US-PGPUB;	İ
		(dioxide oxide)))	EPO; JPO;	
			DERWENT;	ļ
			IBM_TDB	ĺ
-	4	barrase means (deaders mounts) needs mice and (plasma glow	USPAT;	2003/01/09 11:45
		discharge) near9 (polymeri\$ation polymeri\$ing polymeri\$1ed	US-PGPUB;	
		graft\$5) and (silica (silicon near5 (dioxide oxide)))	ЕРО; ЛРО;	
1			DERWENT;	
			IBM_TDB	
-	2	rotat\$5 near9 reactor near9 plasma same (parcticle particulate)	USPAT;	2003/01/09 11:47
1			US-PGPUB;	
			ЕРО; ЛРО;	
ļ			DERWENT;	
f			IBM_TDB	
-	13	(1	USPAT;	2003/01/09 11:50
		(polymeri\$ation polymeri\$ing polymeri\$1ed graft\$5) same (filler	US-PGPUB;	
İ		parcticle particulate powder\$4)	ЕРО; ЛРО;	
			DERWENT;	
	ļ		IBM TDB	
-	1	surface near9 (treat\$9 modif\$9) near9 filler with (plasma glow	USPAT;	2003/01/09 12:23
		discharge) near9 (polymeri\$ation polymeri\$ing polymeri\$1ed	US-PGPUB;	
	1	graft\$5)	ЕРО; ЈРО;	
			DERWENT;	
			IBM TDB	
-	15	filler with (plasma glow discharge) near9 (polymeri\$ation	USPAT;	2003/01/09 17:33
		polymeri\$ing polymeri\$1ed graft\$5)	US-PGPUB;	
		· · · · · · · · · · · · · · · · · · ·	EPO; JPO;	
			DERWENT;	
			IBM TDB	

DERWENT-ACC-NO: 1993-402433 Page 1 of 2

**DERWENT-ACC-**

1993-402433

NO:

DERWENT-

WEEK:

199350

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TITLE:

Polymeric compsn. - contains polyolefin and modified inorganic filler, useful in

mfr. of domestic and industrial articles

INVENTOR: MATKOVSKII, PE; PAPOYAN, AT; RUDAKOV, V

PATENT-

MATKOVSKII, P E PAPOYAN, A T RUDAKOV, V M AS USSR CHEM

ASSIGNEE:

PHYS INST[ASCHR]

PRIORITY-DATA: 1990SU-4880079 (November 5, 1990)

PATENT-FAMILY:

PUB-NO PUB-DATE

LANGUAGE PAGES MAIN-IPC

SU 1776671 A1 November 23, 1992 N/A

005 C08L 023/02

APPLICATION-DATA:

PUB-NO

APPL-DESCRIPTOR APPL-NO

APPL-DATE

SU 1776671A1 N/A

1990SU-4880079 November 5, 1990

INT-CL (IPC): C08F292/00, C08K009/04, C08L023/02

ABSTRACTED-PUB-NO: SU 1776671A

**BASIC-ABSTRACT**:

The compsn. contains in wt.%: modified inorganic filler 20-40; and polyolefin the rest. The <u>filler is modified by polymerisation of saturated and unsaturated hydrocarbons in high-frequency discharge onto the surface of inorganic particles in 0.048-2.120 pts.wt. of polymer to 17.88-39.24 pts.wt. of inorganic filler.</u>

In the examples the filler is from the group contg. technical carbon, graphite, calcite, tafa, kaolin, silicagel, etc. The modification is in thermostat reactor with outer electrodes connected by flexible screened conductors of length 40 cm to generator of frequency 40.68 MHz. Pressure is reduced to 1 Pa by vacuum-pump, the reactor is filled with argon to 0.1 MPa, then argon is pumped out, and the discharge of specific power 0.53 W/cu.cm started in the zone of 0.2 l; ethylene at 20 deg.C in 30 mins. is fed into the discharge zone by capillary at the rate of 0.13 m.mol/min. Modified filler is combined with high-pressure polyethylene in laboratory microrollers at temp. 125 +/-5 deg.C in 5 mins.

USE/ADVANTAGE - Used in filled polyolefin compsns. in the industry of plastic materials that are useful in prodn. of domestic and industrial articles. The physico-mechanical properties are improved. Bul.43/23.11.92

Syntactic foams are produced by dispersing microscopic rigid, hollow or solid particles in a liquid or semi-liquid thermosetting resin and then hardening the system by curing. The particles are generally spheres or microballoons of carbon, polystyrene, phenolic resin, urea-formaldehyde resin, glass, or silica, ranging from 20 to 200 micrometers in diameter. Commercial microspheres have specific gravities ranging from 0.033 to 0.33 for hollow spheres and up to 2.3 for solid glass spheres. The liquid resins used are the usual resins used in molding reinforced articles, e.g., epoxy resin, polyesters, and urea-formaldehyde resins.

PAT-NO:

JP401113454A

DOCUMENT-IDENTIFIER: JP 01113454 A

TITLE:

PRODUCTION OF EPOXY COMPOSITION

PUBN-DATE:

May 2, 1989

**INVENTOR-INFORMATION:** 

NAME

**COUNTRY** 

HAYASHI, TAKAO

**ASSIGNEE-INFORMATION:** 

NAME

COUNTRY

MATSUSHITA ELECTRIC WORKS LTD N/A

APPL-NO:

JP62271051

APPL-DATE: October 26, 1987

INT-CL (IPC):

C08L063/00, C08K009/06

US-CL-CURRENT: 523/213

## ABSTRACT:

PURPOSE: To obtain an epoxy resin composition which can give a cured product of a low modulus, by surface-treating a silica powder to be added to an epoxy resin molding material as a filler by reaction with an epoxysilane and then with an aminosilane and adding this filler to an epoxy resin.

CONSTITUTION: A surface-treated silica [A] is added to an epoxy resin in the production of an epoxy resin composition including a step of adding a silica powder to an epoxy resin, said surfacetreated silica [A] is one formed by reacting the surface of a silica powder with an epoxysilane of formula I and then with an aminosilane of formula II and hydrolyzing the alkoxy groups of the aminosilane. In formulas I and II, R is CH3 or C2H5, R1 is a radical containing an epoxy group, and R2 is a radical containing an amino group.

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DOCUMENT-IDENTIFIER: JP 63130625 A

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PAT-NO:

JР363130625A

**DOCUMENT-**

IDENTIFIER:

JP 63130625 A

TITLE:

EPOXY RESIN COMPOSITION FOR SEALING SEMICONDUCTOR

**DEVICE** 

PUBN-DATE:

June 2, 1988

**INVENTOR-INFORMATION:** 

**NAME** 

COUNTRY

FUJIEDA, SHINETSU

HIRAI, HISASHI

MATSUMOTO, KAZUTAKA

ASSIGNEE-INFORMATION:

NAME

COUNTRY

TOSHIBA CORP N/A

APPL-NO:

JP61276634

APPL-DATE: November 21, 1986

INT-CL (IPC):

C08G059/18, C08G059/18, C08G059/18, C08K005/54, C08K009/06,

C08L063/00, H01L023/30

US-CL-

CURRENT:

<u>523/210</u>

## ABSTRACT:

PURPOSE: To obtain the title composition excellent in heat shock resistance and adhesion of a lead frame to an element, containing an inorganic filler treated with a specified surface treating agent.

CONSTITUTION: 100pts.wt. inorganic filler (a) (e.g., silica) is treated with 0.1 ~ 5 pts.wt. surface treating agent (b) comprising a silane coupling agent (i) (e.g., an epoxy silane coupling agent), a liquid organosiloxane (ii) of a viscosity (20°C) of 500 ~ 1,000,000cP and 0.05 ~ 10pts.wt., per 100pts.wt. component (ii), radical polymerization initiator (iii) (e.g., benzoyl peroxide) to obtain a surface-treated inorganic filler (B). A composition (A) comprising an epoxy resin, a curing agent (accelerator), a mold release, etc., is mixed with component B to obtain the title composition. This composition can be cured by heating to 150°C or above.

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DOCUMENT-IDENTIFIER: JP 01185316 A

Page 1 of 1

PAT-NO:

JP401185316A

DOCUMENT-IDENTIFIER: JP 01185316 A

TITLE:

**EPOXY RESIN MOLDING MATERIAL** 

PUBN-DATE:

July 24, 1989

INVENTOR-INFORMATION:

NAME

COUNTRY

IKEDA, KOJI

KAGAWA, HIROHIKO

TORII, MUNETOMO

**ASSIGNEE-INFORMATION:** 

NAME

COUNTRY

MATSUSHITA ELECTRIC WORKS LTD N/A

APPL-NO:

JP63008002

APPL-DATE: January 18, 1988

INT-CL (IPC):

C08G059/40, C08L063/00

US-CL-CURRENT: 523/456

## ABSTRACT:

PURPOSE: To obtain the title low-stress material of excellent moldability, by mixing an epoxy resin with an inorganic filler, a silicone rubber and, optionally, a crosslinking agent, a curing agent, a cure accelerator, a mold release, a colorant, etc.

CONSTITUTION: A curable epoxy resin (A) having at least two epoxy groups in the molecule is mixed with 30-90wt.% inorganic filler (B) (e.g., silica) option ally surface-treated with a coupling agent and, optionally, 0.5-10wt.% silicone rubber (C) surface-treated with a coupling agent in an amount of 0.05-5wt.% [in terms of the total amount of this coupling agent and the coupling agent used in the surface treatment of component (B)], based on the obtained material, and, optionally, a crosslinking agent, a curing agent, a cure accelerator, a mold release, a colorant, etc., (D).

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DERWENT-

ACC-NO:

2000-406990

DERWENT-

WEEK:

200050

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TITLE:

Modification of spherical shaped silica particle surface for use as catalyst support,

involves coating the surface of silica particles with a graft polymer layer

PATENT-ASSIGNEE: HARAGUCHI T[HARAI], SHOKUBAI KASEI KOGYO KK[NISH]

PRIORITY-DATA: 1998JP-0319573 (November 10, 1998)

PATENT-FAMILY:

**PUB-NO** 

PUB-DATE LANGUAGE PAGES MAIN-IPC

JP 2000143230 A May 23, 2000 N/A

006

C01B 033/18

APPLICATION-DATA:

PUB-NO

APPL-DESCRIPTOR APPL-NO

APPL-DATE

JP2000143230A N/A

1998JP-0319573 November 10, 1998

INT-CL

B01J002/00, B01J019/08, C01B033/18, C08F292/00, C08K003/36, C08K009/04,

(IPC):

C08L101/00

ABSTRACTED-PUB-NO: JP2000143230A

**BASIC-ABSTRACT**:

NOVELTY - The surface of spherical shaped silica particle is modified by coating with a graft polymer layer. The silica particle has a bulk specific gravity of 0.8-1.2 g/ml, pore volume of 0.3 ml/g or less, abrasion strength of 10 weight percentage/15 hours or less and average particle diameter of 20-300 mu m.

DETAILED DESCRIPTION - An INDEPENDENT CLAIM is also included for manufacture of surface modified spherical particle. The surface of spherical shaped silica particles is irradiated with plasma without exposing the particle to atmosphere. Then, the silica particles are made to contact with monomer and graft polymerization was carried out to form a monomer layer on the surface of silica particle.

USE - As catalyst support.

ADVANTAGE - The surface of silica particle is modified by providing a polymer layer by graft polymerization reaction. Therefore, the need of silane coupling process is eliminated.

CHOSEN-DRAWING: Dwg.0/1

DERWENT-CLASS: A14 E36 G02